

**PATENT APPLICATION**  
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q96644

Hideo KOBAYASHI

Appln. No.: 10/590,663

Group Art Unit: 1756

Confirmation No.: 2137

Examiner: not yet assigned

Filed: June 1, 2007

For: METHOD OF MANUFACTURING PHOTOMASK BLANK

**REQUEST FOR CORRECTED OFFICIAL FILING RECEIPT**

**ATTN:** Office of Initial Patent Examination  
Filing Receipt Correction  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

We enclose a copy of the Official Filing Receipt for the above-identified application and request the following correction:

**Assignment For Published Patent Application:** Hoya Corporation

Verification for the requested correction is indicated on the Assignment filed June 1, 2007.

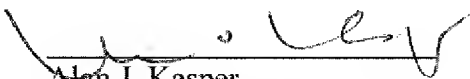
Respectfully submitted,

SUGHRUE MION, PLLC  
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WASHINGTON OFFICE

**23373**

CUSTOMER NUMBER

  
Alan J. Kasper  
Registration No. 25,426

Date: October 11, 2007



## UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE  
 United States Patent and Trademark Office  
 Address: COMMISSIONER FOR PATENTS  
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APPL NO.	FILING OR 371(c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	TOT CLMS	IND CLMS
10/590,663	06/01/2007	1756	1230	Q96644	8	4

23373  
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 2100 PENNSYLVANIA AVENUE, N.W.  
 SUITE 800  
 WASHINGTON, DC 20037

**DOCKETED**

SEP 12 2007

CONFIRMATION NO. 2137

**FILING RECEIPT**

\*OC000000025754706\*

Date Mailed: 09/11/2007

Receipt is acknowledged of this nonprovisional patent application. The application will be taken up for examination in due course. Applicant will be notified as to the results of the examination. Any correspondence concerning the application must include the following identification information: the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. **If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Filing Receipt Corrections. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).**

**Applicant(s)**

Hideo Kobayashi, Kofu-shi, JAPAN;

**Assignment For Published Patent Application: Hoya Corporation****Power of Attorney:** The patent practitioners associated with Customer Number 23373.**Domestic Priority data as claimed by applicant**

This application is a 371 of PCT/JP04/02814 03/05/2004

**Foreign Applications**

JAPAN 2002-234282 08/12/2002

**If Required, Foreign Filing License Granted:** 08/31/2007

**The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is** **US10/590,663**

**Projected Publication Date:** 12/20/2007**Non-Publication Request:** No**Early Publication Request:** No

**Title**

Method of Manufacturing Photomask Blank

**Preliminary Class**

430

**PROTECTING YOUR INVENTION OUTSIDE THE UNITED STATES**

Since the rights granted by a U.S. patent extend only throughout the territory of the United States and have no effect in a foreign country, an inventor who wishes patent protection in another country must apply for a patent in a specific country or in regional patent offices. Applicants may wish to consider the filing of an international application under the Patent Cooperation Treaty (PCT). An international (PCT) application generally has the same effect as a regular national patent application in each PCT-member country. The PCT process **simplifies** the filing of patent applications on the same invention in member countries, but **does not result** in a grant of "an international patent" and does not eliminate the need of applicants to file additional documents and fees in countries where patent protection is desired.

Almost every country has its own patent law, and a person desiring a patent in a particular country must make an application for patent in that country in accordance with its particular laws. Since the laws of many countries differ in various respects from the patent law of the United States, applicants are advised to seek guidance from specific foreign countries to ensure that patent rights are not lost prematurely.

Applicants also are advised that in the case of inventions made in the United States, the Director of the USPTO must issue a license before applicants can apply for a patent in a foreign country. The filing of a U.S. patent application serves as a request for a foreign filing license. The application's filing receipt contains further information and guidance as to the status of applicant's license for foreign filing.

Applicants may wish to consult the USPTO booklet, "General Information Concerning Patents" (specifically, the section entitled "Treaties and Foreign Patents") for more information on timeframes and deadlines for filing foreign patent applications. The guide is available either by contacting the USPTO Contact Center at 800-786-9199, or it can be viewed on the USPTO website at <http://www.uspto.gov/web/offices/pac/doc/general/index.html>.

For information on preventing theft of your intellectual property (patents, trademarks and copyrights), you may wish to consult the U.S. Government website, <http://www.stopfakes.gov>. Part of a Department of Commerce initiative, this website includes self-help "toolkits" giving innovators guidance on how to protect intellectual property in specific countries such as China, Korea and Mexico. For questions regarding patent enforcement issues, applicants may call the U.S. Government hotline at 1-866-999-HALT (1-866-999-4158).

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Title 37, Code of Federal Regulations, 5.11 & 5.15**

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## Assignment

Whereas, I/We, HIDEO KOBAYASHI of Kofu-shi, Yamanashi, Japan, hereinafter called assignor(s), have invented certain improvements in

PHOTOMASK BLANK MANUFACTURING METHOD

as set forth in an application for Letters Patent of the United States of America corresponding to international application No. PCT/JP2004/002814 filed on March 5, 2004; and

Whereas, HOYA CORPORATION,

7-5, Naka-Ochiai 2-chome, Shinjuku-ku, Tokyo 161-8525, Japan

(assignee), desires to acquire the entire right, title, and interest in the application and invention, and to any United States patents to be obtained therefor;

Now therefore, for valuable consideration, receipt whereof is hereby acknowledged,

I/We, the above named assignor(s), hereby sell, assign and transfer to the above named assignee, its successors and assigns, the entire right, title and interest in the application and the invention disclosed therein for the United States of America, including the right to claim priority under 35 U.S.C. §119, and I/we request the Director – U.S. Patent and Trademark Office to issue any Letters Patent granted upon the invention set forth in the application to the assignee, its successors and assigns; and I/we will execute without further consideration all papers deemed necessary by the assignee in connection with the United States application when called upon to do so by the assignee.

I/We hereby authorize and request our attorneys SUGHRUE MION, PLLC of 2100 Pennsylvania Avenue, NW, Washington, DC 20037-3213 to insert here in parentheses (Application number \_\_\_\_\_ and Confirmation number \_\_\_\_\_, filed \_\_\_\_\_) the filing date and application number of said application when known.

Date: September 6, 2006

  
s/ HIDEO KOBAYASHI

Date: \_\_\_\_\_

s/

Date: \_\_\_\_\_

s/

Date: \_\_\_\_\_

s/

Date: \_\_\_\_\_

s/